

11120 PME 544200 微奈米製造技術:

111200 PME 544200 Micro and Nano Fabrication Technology

上課時間: F5F6F7

地點: 台達館 321 教室 (若疫情嚴峻, 可能改採線上)

This course will be offered in English (英語授課)

Chien-Chung Fu 傅建中

Syllabus

Week	Date	Syllabus 課程安排
1	2023.02.17	Introduction and Opening the Course
2	2023.02.24	梅竹賽停課
3	2023.03.03	X-Ray Mask and X-Ray Lithography I
4	2023.03.10	E-beam and RIE
5	2023.03.17	Photoresists and Development
6	2023.03.24	Lithography in Semiconductor
7	2023.03.31	Break
8	2023.04.07	Galvanic Deposition
9	2023.04.14	期中考
10	2023.04.21	Plastic Molding in the LIGA Process
11	2023.04.28	Interference Lithography and NIL
12	2023.05.05	Mid-Term Report I
13	2023.05.12	Mid-Term Report II
14	2023.05.19	Mid-Term Report III
15	2023.05.26	Company Visiting
16	2023.06.02	Break
17	2023.06.09	Final Exam

Grading: (Grading will be based on the ranking in the class)

期中考: 25%

期中報告: 25%

每週報告與上課參與: 30%

期末考: 20%

Textbook: Microsystem Technology, W. Menz, J. Mohr, O. Paul, Wiley-VCH Ch.7~Ch.10

Mid-Term Report/Supplementary Material:

1. LIGA and its Applications, Brand et al., Wiley-VCH Ch.8-Ch.19.
2. Multiphoton Lithography, Jürgen Stampfl, Robert Liska, and Aleksandr Ovsianikov, Wiley-VCH, CH6-CH9(material), CH10-CH14(application)

註一：關於疫情，本學期這門課將以實體上課，上課的教室將在台達館 321 教
若學期中，國內疫情變嚴峻，依 CDC 的規定，有可能視情況改成遠距上課。

註二：每週心得上傳時限當週二中午 12 點，從 EECLASS 系統。

確認修本門課的同學，屆時請加入本課程 line 群組：